

film, and moreover that the brightness and contrast of an image formed are lowered when it is intended to reduce the metallic gloss of the reflecting electrode. It is also conducted to provide irregularities in the reflecting electrode itself to impart light diffusing properties thereto. There have been known, for examples, a method in which a heat, honing or etching treatment is conducted after formation of a reflecting layer, an example that a reflecting layer is formed after a honing treatment, which is disclosed in Japanese Patent Application Laid-Open No. 212931/1992, and an example that a reflecting layer is provided after irregularities are formed by electron beam deposition, CVD or plasma CVD, which is disclosed in Japanese Patent Application Laid-Open No. 315129/1992. However, these cases have involved a problem that the treatments thereof are complicated, and so it is difficult to control the degree of the irregularities with good reproducibility. In addition, Japanese Patent Application Laid-Open Nos. 267220/1992 and 308816/1992 disclose an example that a thin metal film is provided on irregularities formed by applying an organic insulating film to which fine particles have been added. The mere application of a coating containing the fine particles fails to uniformly arrange the fine particles at a high density like the typical drawings shown in these publications. Accordingly, it is difficult to achieve reflection properties uniform and high in reproducibility.